Supporting Information

Boosting Plasmon-Enhanced Electrochemistry by In-Situ Surface Cleaning of Plasmonic Nanocatalysts

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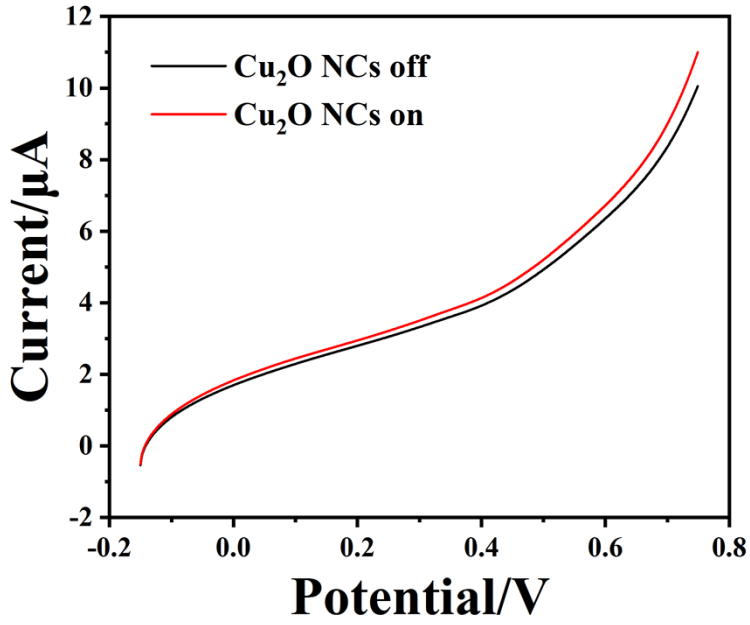

Figure S1. Forward scan curves of CVs for 50 mM glucose oxidation (in 0.1 M NaOH) on the Cu_2O NCs/GC with and without LSPR excitation.

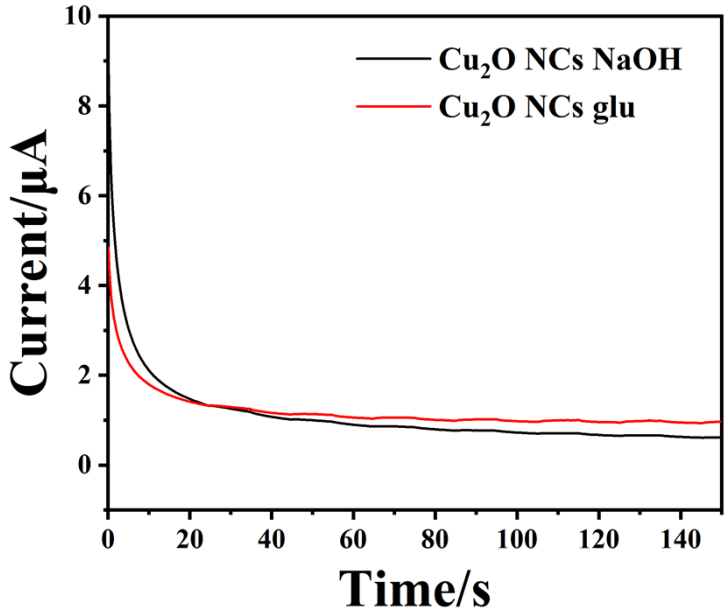

Figure S2. I-t curves at 0.3 V with plasmonic excitation on and off in the presence and absence of 50 mM glucose at the Cu_2O NCs/GC.